PATENT ASSIGNMENT COVER SHEET

Electronic Version v1.1 Stylesheet Version v1.2 EPAS ID: PAT3928625

SUBMISSION TYPE:	NEW ASSIGNMENT
NATURE OF CONVEYANCE:	RELEASE OF SECURITY INTEREST

CONVEYING PARTY DATA

Name	Execution Date
CREDIT SUISSE, AG, CAYMAN ISLANDS BRANCH	06/21/2016

RECEIVING PARTY DATA

Name:	AVANTOR PERFORMANCE MATERIALS, INC.
Street Address:	222 RED SCHOOL LANE
City:	PHILLIPSBURG
State/Country:	NEW JERSEY
Postal Code:	08865

PROPERTY NUMBERS Total: 57

Property Type	Number
Patent Number:	6203679
Patent Number:	5217619
Patent Number:	5308745
Patent Number:	6749998
Patent Number:	6326130
Patent Number:	5466389
Patent Number:	5498293
Patent Number:	5576217
Patent Number:	5989353
Patent Number:	6585825
Patent Number:	6465403
Patent Number:	6599370
Patent Number:	6311134
Patent Number:	6899818
Patent Number:	6875817
Patent Number:	7393819
Patent Number:	7247208
Patent Number:	7718591
Patent Number:	7419945
Patent Number:	7671001

PATENT REEL: 039111 FRAME: 0908

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Property Type	Number
Patent Number:	7470767
Patent Number:	7928046
Patent Number:	7521406
Patent Number:	7767636
Patent Number:	7754668
Patent Number:	7825078
Patent Number:	7947639
Patent Number:	7951764
Patent Number:	7799749
Patent Number:	7375188
Application Number:	11813434
Application Number:	11817874
Application Number:	12565172
Application Number:	11910281
Application Number:	11521246
Application Number:	12046582
Application Number:	12522605
Application Number:	12522716
Application Number:	12596921
Application Number:	12600369
Application Number:	12619259
Application Number:	10515372
Application Number:	61155309
Application Number:	61357146
Application Number:	12811257
Application Number:	61401808
Application Number:	12737663
Application Number:	12998296
Application Number:	12998499
Application Number:	13066889
Application Number:	61518305
Application Number:	61518258
Application Number:	12998655
Application Number:	12998659
Application Number:	12998656
Application Number:	61519902
Application Number:	11630603

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ATTORNEY DOCKET NUMBER:	217730/2332
NAME OF SUBMITTER:	MOHAMMED A. ALVI
SIGNATURE:	/Mohammed A. Alvi/
DATE SIGNED:	06/21/2016

Total Attachments: 11

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RELEASE OF SECURITY INTEREST IN PATENT COLLATERAL

This RELEASE OF SECURITY INTEREST IN PATENT COLLATERAL, dated as of June 21, 2016 (this "Release"), is made by CREDIT SUISSE AG, CAYMAN ISLANDS BRANCH, as collateral agent (in such capacity, the "Collateral Agent"), in favor of AVANTOR PERFORMANCE MATERIALS, INC., a New Jersey corporation (the "Grantor"), as follows:

WITNESSETH

WHEREAS, pursuant to the (a) Patent Security Agreement, dated as of October 8, 2010 (the "2010 Patent Security Agreement"), and recorded with the U.S. Patent and Trademark Office on October 8, 2010 at Reel/Frame 25114/208; (b) Patent Security Agreement, dated as of June 24, 2011 (the "2011 Patent Security Agreement"), and recorded with the U.S. Patent and Trademark Office on June 24, 2011 at Reel/Frame 26499/256; and (c) Patent Security Agreement, dated as of October 1, 2014 (the "2014 Patent Security Agreement"), and recorded with the U.S. Patent and Trademark Office on October 3, 2014 at Reel/Frame 33882/488, as security for the payment or performance, as the case may be, in full of the Obligations, the Grantor pledged to the Collateral Agent, its successors and assigns, for the ratable benefit of the Secured Parties, and granted to the Collateral Agent, its successors and assigns, for the ratable benefit of the Secured Parties, a security interest in all right, title or interest in or to any and all of the following assets and properties then owned or at any time thereafter acquired by the Grantor or in which the Grantor then had or at any time in the future may acquire any right, title or interest (collectively, the "Released Patent Collateral"):

- (a) all patents issued by the United States or the equivalent thereof in any other country, and all applications for patents of the United States or the equivalent thereof in any other country, including issued patents and pending applications in the United States Patent and Trademark Office (or any successor or any similar offices in any other country), including those listed on Schedule I thereto;
- (b) all reissues, continuations, divisions, continuations-in-part, renewals or extensions thereof, and the inventions disclosed or claimed therein, including the right to make, use and/or sell the inventions disclosed or claimed therein; and
- (c) all Proceeds and products of any and all of the foregoing, all Supporting Obligations and all collateral security and guarantees given by any Person with respect to any of the foregoing; and

WHEREAS, the Grantor has requested that the Collateral Agent release its security interest in all of the Grantor's right, title or interest in or to the Released Patent Collateral.

NOW, THEREFORE, the Collateral Agent, without recourse, representation or warranty of any kind or nature, and at the Grantor's sole cost and expense, hereby terminates, cancels and releases its security interest in all of the Grantor's right, title and interest in or to the Released Patent Collateral, including the patents listed on Schedules A, B and C hereto, and any and all

right, title and interest of the Collateral Agent in the Released Patent Collateral shall hereby terminate, cease and become void.

The Collateral Agent authorizes and requests that the Commissioner of Patents and Trademarks and any other applicable government officer record this Release.

THIS RELEASE SHALL BE CONSTRUED IN ACCORDANCE WITH AND GOVERNED BY THE LAWS OF THE STATE OF NEW YORK.

Capitalized terms used but not defined herein shall have the meanings given to them in the 2010 Patent Security Agreement, 2011 Patent Security Agreement or 2014 Patent Security Agreement, as applicable.

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IN WITNESS WHEREOF, the Collateral Agent has caused this Release to be duly executed and delivered by its duly authorized officer as of the date first written above.

CREDIT SUISSE AG, CAYMAN ISLANDS BRANCH,

as Collateral Agent

By:

Name: Mikhail Faybusovich Title: Authorized Signatory

By:

Name: Whitney Gaston

Title: Authorized Signatory

[SIGNATURE PAGE TO PATENT RELEASE]

SCHEDULE A TO RELEASE OF SECURITY INTEREST IN PATENT COLLATERAL

Patents and Patent Applications

Reel/Frame No. 25114/208

Title	App. No.	Filing	Patent No.	Issue Date
		Date		
Electrophoresis Gel Container	09/251129	16-Feb-99	6203679	20-May- 01
Liquid-Solid Extraction Apparatus and Method of Using Same	07/846895	06-Mar-92	5217619	08-Jun-93
Alkaline-Containing Photoresist Stripping Compositions Producing Reduced Metal Corrosion with Cross-Linked or Hardened Resist Resins	07/972511	06-Nov-92	5308745	03-May- 94
Photoresist Strippers Containing Reducing Agents to Reduce Metal Corrosion	09/968665	02-Oct-01	6749998	15-Jun-04
Photoresist Strippers Containing Reducing Agents to Reduce Metal Corrosion	08/133680	07-Oct-93	6326130	04-Dec-01
pH Adjusted Surfactant-Containing Alkaline Cleaner Composition for Cleaning Microelectronics Substrates	08/230132	20-Apr-94	5466389	14-Nov-95
Cleaning Wafer Substrates of Metal Contamination While Maintaining Wafer Smoothness	08/264858	23-Jun-94	5498293	12-Mar-96
Solid Phase Micro-Extraction of Trace Amounts of Organic Analytes	08/396124	28-Feb-95	5576217	19-Nov-96
Cleaning Wafer Substrates of Metal Contamination While Maintaining Wafer Smoothness	08/729565	11-Oct-96	5989353	23-Nov-99
Stabilized Alkaline Compositions for Cleaning Microelectronic Substrates	09/688559	16-Oct-00	6585825	01-Jul-03
Silicate-Containing Alkaline Compositions for Cleaning Microelectronic Substrates	09/701114	17-Nov-00	6465403	15-Oct-02
Stabilized Alkaline Compositions for Cleaning Microelectronic Substrates	09/859142	16-May- 01	6599370	29-Jul-03
Process and Apparatus for Comparing Chemical Products	09/247058	09-Feb-99	6311134	30-Oct-01
Method and Composition for Removing Sodium- Containing Material from Microcircuit Substrates	10/220720	04-Sep-02	6899818	31-May- 05
Functionalized Polymeric Media for Separation of Analytes	10/250570	12-Feb-03	6875817	05-Apr-05
Ammonia-Free Alkaline Microelectronic Cleaning Compositions with Improved Substrate Compatibility	10/483037	06-Jan-04	7393819	01-Jul-08

Title	App. No.	Filing	Patent No.	Issue Date
	101102026	Date	53.53 00	217105
Microelectronic Cleaning Compositions Containing	10/483036	06-Jan-04	7247208	24-Jul-07
Ammonia-Free Fluoride Salts for Selective Photoresist				
Stripping and Plasma Ash				
Microelectronic Cleaning Compositions Containing	11/762087	13-Jun-07	7718591	18-May-
Ammonia-Free Fluoride Salts for Selective Photoresist	117.02007	10 0411 01	,,,100,,1	10
Stripping and Plasma Ash				
Microelectronic Cleaning Compositions Containing	10/515392	22-Nov-04	7419945	02-Sep-08
Oxidizers and Organic Solvents	10/550000	22.16	5 (5 1001	02.74
Alkaline, Post Plasma Etch or Post Etch/Ash Residue	10/572860	22-Mar-06	7671001	02-Mar-10
Removers and Photoresist Strippers Containing Metal-Halide Corrosion Inhibitors				
Preparation of Ultrapure Polymeric Articles	11/631586	04-Jan-07	7470767	30-Dec-08
Preparation and Use of Mixed Mode Polymeric	11/813434	06-Jul-07	7170707	30 Bec 00
Chromatographic Media for Bioseparations				
Stripping and Cleaning Compositions for	11/349635	08-Feb-06	7928046	19-Apr-11
Microelectronics	10/002220	05.31	7521406	21 1 00
Microelectric Cleaning Composition Containing Halogen Oxygen Acids, Salts and Derivatives	10/982330	05-Nov-04	7521406	21-Apr-09
Oxygen Acids, Sans and Derivatives				
Nanoelectronic and Microelectronic Cleaning Compositions	10/584827	27-Jun-06	7767636	03-Aug-10
Transcrete and Price deceronic Cleaning Compositions	10/30/1027	27 3411 00	7,0,050	05 1145 10
Compositions for the Removal of Post-Etch and Ashed	11/911346	12-Oct-07	7754668	13-Jul-10
Photoresist Residue and Bulk Photoresist				
	11/500500	• • • • • • • • • • • • • • • • • • • •		
Composition for Cleaning Microelectronic Substrates	11/630603	20-Dec-06		
Non-Aqueous Stripping Composition Containing Fructose	11/630602	20-Dec-06	7825078	27-Oct-06
Tron requestes outpping composition containing reaction	11/03/0002	20 200	7023070	27 361 33
Non-Aqueous, Non-Corrosive Microelectronic Cleaning	11/719690	18-May-	7947639	24-May- 11
Compositions Containing Polymeric Corrosion Inhibitors		07		Ĭ
	11/01/70/74	06.6.07		
Compositions for Cleaning Ion Implanted Photoresist in Front End of Line Applications	11/817874	06-Sep-07		
High Efficiency Chromatography Column With Re-Usable	12/565172	23-Sep-09		
End Cap	12/303172	23-3ср-09		
Non-Aqueous, Non-Corrosive Microelectronic Cleaning	11/720084	24-May-	7951764	31-May- 11
Compositions		07		
Non-Aqueous Photoresist Stripper That Inhibits	11/910281	01-Oct-07		
Galvanic Corrosion	124151005			
Stabilized, Non-Aqueous Cleaning Compositions for	12/161886	23-Jul-08	7799749	21-Sep-10
Microelectronics Substrates Purified Vegetarian Protein A And Process For Production	11/521246	14-Sep-06		
Thereof	11/3/1/40	14-2ch-00		
Purified Vegetarian Protein A And Process For Production	11/194093	29-Jul-05	7375188	20-May-
Thereof Vegetarian				08
Purified Vegetarian Protein A And Process For Production	12/046582	12-Mar-08		
Thereof				
Chromatographic Media and Chromatographic Equipment	12/522605	09-Jul-09		
Storage Solutions and Use Thereof	<u> </u>			

Title	App. No.	Filing	Patent No.	Issue Date
		Date		
Peroxide Activated Oxometalate Based Formulations for	12/522716	10-Jul-09		
Removal of Etch Residues				
Polysilicon Planarization Solution For Planarizing Low	12/596921	21-Oct-09		
Temperature Poly-Silicon Thin Film Panels				
Directly Compressible High Functionality Granular	12/600369	16-Nov-09		
Microcrystalline Cellulose Based Excipient, Manufacturing				
Process and Use Thereof				
Directly Compressible Granular	12/619259	16-Nov-09		
Microcrystalline Cellulose Based Excipient, Manufacturing				
Process and Use Thereof				

SCHEDULE B TO RELEASE OF SECURITY INTEREST IN PATENT COLLATERAL

Patents and Patent Applications

Reel/Frame No. 26499/256

Title	App. No.	Filing Date	Patent No.	Issue Date
Electrophoresis Gel Container	09/251129	16-Feb-99	6203679	20-May- 01
Liquid-Solid Extraction Apparatus and Method of Using Same	07/846895	06-Mar-92	5217619	08-Jun-93
Alkaline-Containing Photoresist Stripping Compositions Producing Reduced Metal Corrosion with Cross-Linked or Hardened Resist Resins	07/972511	06-Nov-92	5308745	03-May- 94
Photoresist Strippers Containing Reducing Agents to Reduce Metal Corrosion	09/968665	02-Oct-01	6749998	15-Jun-04
Photoresist Strippers Containing Reducing Agents to Reduce Metal Corrosion	08/133680	07-Oct-93	6326130	04-Dec-01
pH Adjusted Surfactant-Containing Alkaline Cleaner Composition for Cleaning Microelectronics Substrates	08/230132	20-Apr-94	5466389	14-Nov-95
Cleaning Wafer Substrates of Metal Contamination While Maintaining Wafer Smoothness	08/264858	23-Jun-94	5498293	12-Mar-96
Solid Phase Micro-Extraction of Trace Amounts of Organic Analytes	08/396124	28-Feb-95	5576217	19-Nov-96
Cleaning Wafer Substrates of Metal Contamination While Maintaining Wafer Smoothness	08/729565	11-Oct-96	5989353	23-Nov-99
Stabilized Alkaline Compositions for Cleaning Microelectronic Substrates	09/688559	16-Oct-00	6585825	01-Jul-03
Silicate-Containing Alkaline Compositions for Cleaning Microelectronic Substrates	09/701114	17-Nov-00	6465403	15-Oct-02
Stabilized Alkaline Compositions for Cleaning Microelectronic Substrates	09/859142	16-May- 01	6599370	29-Jul-03
Process and Apparatus for Comparing Chemical Products	09/247058	09-Feb-99	6311134	30-Oct-01
Method and Composition for Removing Sodium- Containing Material from Microcircuit Substrates	10/220720	04-Sep-02	6899818	31-May- 05
Functionalized Polymeric Media for Separation of Analytes	10/250570	12-Feb-03	6875817	05-Apr-05
Ammonia-Free Alkaline Microelectronic Cleaning Compositions with Improved Substrate Compatibility	10/483037	06-Jan-04	7393819	01-Jul-08

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Title	App. No.	Filing Date	Patent No.	Issue Date
Microelectronic Cleaning Compositions Containing Ammonia-Free Fluoride Salts for Selective Photoresist Stripping and Plasma Ash	10/483036	06-Jan-04	7247208	24-Jul-07
Microelectronic Cleaning Compositions Containing Ammonia-Free Fluoride Salts for Selective Photoresist Stripping and Plasma Ash	11/762087	13-Jun-07	7718591	18-May- 10
Microelectronic Cleaning Compositions Containing Oxidizers and Organic Solvents	10/515392	22-Nov-04	7419945	02-Sep-08
Alkaline, Post Plasma Etch or Post Etch/Ash Residue Removers and Photoresist Strippers Containing Metal-Halide Corrosion Inhibitors	10/572860	22-Mar-06	7671001	02-Mar-10
Preparation of Ultrapure Polymeric Articles	11/631586	04-Jan-07	7470767	30-Dec-08
Preparation and Use of Mixed Mode Polymeric Chromatographic Media for Bioseparations	11/813434	06-Jul-07		
Stripping and Cleaning Compositions for Microelectronics	11/349635	08-Feb-06	7928046	19-Apr-11
Microelectric Cleaning Composition Containing Halogen Oxygen Acids, Salts and Derivatives	10/982330	05-Nov-04	7521406	21-Apr-09
Nanoelectronic and Microelectronic Cleaning Compositions	10/584827	27-Jun-06	7767636	03-Aug-10
Compositions for the Removal of Post-Etch and Ashed Photoresist Residue and Bulk Photoresist	11/911346	12-Oct-07	7754668	13-Jul-10
Composition for Cleaning Microelectronic Substrates	11/630603	20-Dec-06		
Non-Aqueous Stripping Composition Containing Fructose	11/630602	20-Dec-06	7825078	27-Oct-06
Non-Aqueous, Non-Corrosive Microelectronic Cleaning Compositions Containing Polymeric Corrosion Inhibitors	11/719690	18-May- 07	7947639	24-May- 11
Compositions for Cleaning Ion Implanted Photoresist in Front End of Line Applications	11/817874	06-Sep-07		
High Efficiency Chromatography Column With Re-Usable End Cap	12/565172	23-Sep-09		
Non-Aqueous, Non-Corrosive Microelectronic Cleaning Compositions	11/720084	24-May- 07	7951764	31-May- 11
Non-Aqueous Photoresist Stripper That Inhibits Galvanic Corrosion	11/910281	01-Oct-07		
Stabilized, Non-Aqueous Cleaning Compositions for Microelectronics Substrates	12/161886	23-Jul-08	7799749	21-Sep-10
Purified Vegetarian Protein A And Process For Production Thereof	11/521246	14-Sep-06		
Purified Vegetarian Protein A And Process For Production Thereof Vegetarian	11/194093	29-Jul-05	7375188	20-May- 08
Purified Vegetarian Protein A And Process For Production Thereof	12/046582	12-Mar-08		
Chromatographic Media and Chromatographic Equipment Storage Solutions and Use Thereof	12/522605	09-Jul-09		

Title	App. No.	Filing	Patent No.	Issue Date
		Date		
Peroxide Activated Oxometalate Based Formulations for Removal of Etch Residues	12/522716	10-Jul-09		
Polysilicon Planarization Solution For Planarizing Low Temperature Poly-Silicon Thin Film Panels	12/596921	21-Oct-09		
Directly Compressible High Functionality Granular Microcrystalline Cellulose Based Excipient, Manufacturing Process and Use Thereof	12/600369	16-Nov-09		
Directly Compressible Granular Microcrystalline Cellulose Based Excipient, Manufacturing Process and Use Thereof	12/619259	16-Nov-09		
Microelectronic Cleaning and Arc Remover Compositions	10/515372	22-Nov-04		
Multipurpose Acidic Organic Solvent Based Microelectronic Cleaning Composition	61/155309	25-Feb-09		
Metal Sulfide Deposition Using Alkylated Thioureas	61/357146	22-Jun-10		
Post Plasma Etch/Ash Residue and Silicon- Based Anti- Reflective Coating Remover Compositions Containing Tetrafluoroborate Ion	12/811257	30-Jun-10		
Chemical Solutions for Texturing of Multicrystalline Silicone Wafers for Solar Cell Manufacturing	61/401808	19-Aug-10		
Sustained Release Composition	12/737663	04-Feb-11		
Aqueous Acidic Formulations for Copper Oxide Etch Residue Removal and Prevention of Copper	12/998296	06-Apr-11		
Gluconic Acid-Containing Microelectronics Stripping and Cleaning Composition	12/998499	27-Apr-11		
Non-Aqueous, Non-Corrosive Photoresist Stripper Containing Polymer Having Multiple Amino and/or Hydroxyl Functional Groups	13/066889	27-Apr-11		
Separation of Protein Monomers and Aggregates by Weak Anion Exchangers	61/518305	03-May- 11		
A Novel Chromatographic Media Based on Alkyamine Spacer, Synthesis and Use Thereof	61/518258	03-May- 11		
Directly Compressible High Functionality Granular Dibasic Calcium Phosphate Based Co-Processed Excipient.	12/998655	16-May- 11		
Directly Compressible Granular Microcrystalline Cellulose Co- Processed Excipient and Process To	12/998659	16-May- 11		
New Chromatographic Media Based On Phenoxy Alkyl And Alkoxy-Or Phenoxy-Phenyl Alkyl Ligands	12/998656	16-May- 11		
	l			

Title	App. No.	Filing Date	Patent No.	Issue Date
Solvent Based Polymer Removal Chemistry With Enhanced	61/519902	01-Jun-11		
Compatability With Copper Metallization And Porous Low-K				
Dielectrics				

SCHEDULE C TO RELEASE OF SECURITY INTEREST IN PATENT COLLATERAL

Patents and Patent Applications

Reel/Frame No. 33882/488

Title	App. No.	Filing Date	Patent No.	Issue Date
Microelectronic cleaning and arc remover compositions	10515372	22-Nov-04	8906838	9-Dec-14
Compositions and methods for texturing polycrystalline silicon wafers	13778856	27-Feb-13	8986559	24-Mar-15
Chromatographic media	14066251	29-Oct-13		
Separation of protein monomers from aggregates by solid weak anion exchange support functionalized with amine moieties	13373064	3-Nov-11		
Novel chromatographic media based on allylamine and its derivative for protein purification	14115238	16-Apr-14		
Microelectronic substrate cleaning compositions having copper/azole polymer inhibition	14348955	1-Apr-14		
Semi-aqueous polymer removal compositions with enhanced compatibility to copper, tungsten, and porous low-k dielectrics	14122793	8-May-14	9327966	3-May-16
Mounting medium	09968043	2-Oct-01	6709836	23-Mar-04
Karl fischer reagent	09979313	11-Mar-02	7247485	24-Jul-07
Preparation of ultrapure polymeric articles	11631586	04-Jan-07	7470767	30-Dec-08
Mounting medium	10628456	29-Jul-03	6913902	5-Jul-05
Multipurpose acidic, organic solvent based microelectronic cleaning composition	13138467	22-Aug-11	8557757	15-Oct-13
Stripping compositions for cleaning ion implanted photoresist from semiconductor device wafers	13138468	22-Aug-11	8497233	30-Jul-13
Solution for increasing wafer sheet resistance and/or photovoltaic cell power density level	13138144	12-Jul-11	8366954	5-Feb-13
Orally disintegrating tablets	12270905	14-Nov-08	8545890	1-Oct-13

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